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CHE323/CHE384
Chemical Processes for Micro- and Nanofabrication
www.lithoguru.com/scientist/CHE323

Lecture 20 Evaporation, part 1

Chris A. Mack
Adjunct Associate Professor

Reading:
Chapter 12, *Fabrication Engineering at the Micro- and Nanoscale*, 4th edition, Campbell

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Deposition Techniques

- Electrochemical Deposition
 - Copper for multilevel metallization
- Chemical vapor deposition (CVD)
 - Chemical reactions on the wafer surface result in film deposition
- Physical vapor deposition (PVD)
 - Sputtering
 - Evaporation

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Evaporation

- Early technique, less common today
- Operation performed in vacuum
- The “charge” (material to be evaporated) is placed in a crucible and heated until it melts
- Evaporated material spreads in all directions
- When vapor hits cold wafer, it sticks, depositing film
- Commonly used for metal deposition

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Evaporation

Wafers arranged in planetarium

Bell Jar

Roughing Pump

Diffusion or Cryopump

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Options for Melting the Charge

- Run current through the crucible (e.g., tungsten)
 - Problem: if melting point of charge is high (e.g, refractory metals), crucible will sublimate, contaminating the deposition and the charge
- Inductively heat the charge (RF energy)
 - Reduces but does not eliminate crucible heating
- E-beam evaporation

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E-beam Evaporation

- Electrons bombard the charge, causing it to locally heat up. Crucible is cooled – melt is surrounded by solid charge
 - Problem: X-rays and secondary electrons are generated, which can damage the wafer, cause trapped charge in gate oxide, etc.

Electron path

Magnetic Field

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E-Beam Evaporation Source



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Depositing Alloys

- Use alloy charge
 - Problem: different alloy components melt at different temperatures
- Use multiple crucibles, independently heated
 - Problem: hard to control deposition rates well enough to get consistent composition

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Deposition Control

- Deposition rates are a strong function of melt temperature (difficult to control)
- Solution: process control
 - Measure deposited thickness in real time
 - When thickness reaches target, close shutter
- Thickness measurement:
 - Quartz crystal microbalance
 - Frequency of oscillation is proportional to mass of deposited material (and thus thickness)

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Evaporation Equipment



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Lecture 20: What have we learned?

- What are the three common deposition methods used in semiconductor manufacturing?
- What are the different methods for melting the charge, and their advantages and disadvantages?
- Explain how e-beam evaporation works
- How is film thickness controlled in evaporation systems?

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